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# Synthesis of MoS2 from [Mo3S7(S2CNEt2)3]I for Enhancing Photoelectrochemical Performance and Stability of Cu2O Photocathode Toward Efficient Solar Water Splitting

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Cu<sub>2</sub>O is a typical *p*-type semiconductor that can efficiently absorb visible light and has a high absorption coefficient due to its narrow forbidden band. Thus, it finds potential applications in solar energy conversion and photocatalysis. However, Cu<sub>2</sub>O photocathodes suffer from a major issue of chemical stability and sluggish proton reduction for splitting water using sunlight. We present here a facile method of coating a MoS<sub>2</sub> layer onto Cu<sub>2</sub>O to significantly improve its stability and proton reduction efficiency. MoS<sub>2</sub> coating on top of Cu<sub>2</sub>O is achieved from spin coating [Mo<sub>3</sub>S<sub>7</sub>(S<sub>2</sub>CNEt<sub>2</sub>)<sub>3</sub>] combined with a thermal annealing process to obtain the optimal stoichiometry. MoS<sub>2</sub> films synthesized using this method show good prospects as both a protection layer and an electrocatalyst for hydrogen evolution reactions (HER) due to excellent stability and high electrocatalytic activity. The proton reduction performance of spin-coated MoS<sub>2</sub>/FTO electrodes is studied to determine the optimal synthesis conditions using various derivatives of MoS<sub>2</sub> precursors. Our study suggests that the rate-limiting kinetic step of MoS<sub>2</sub> synthesized in this method is the desorption of adsorbed hydrogen atoms to form molecular hydrogen, and that nanocrystalline MoS<sub>2</sub> with copiously exposed S edges are more active for HER. Photoelectrochemical measurements demonstrate the highest activity for 3-layered (<40 nm thick) MoS<sub>2</sub>/Cu<sub>2</sub>O photocathode fabricated at 450°C with a photocurrent of ~ 6.5 mA cm<sup>-2</sup> at -0.2 V vs. RHE. Additionally, the MoS<sub>2</sub> coating helps minimize the dark current of the Cu<sub>2</sub>O photocathode.

## Introduction

The rising concerns over the increasing global energy demand and negative impact on the environment of fossil fuels have stimulated great efforts towards developing clean and renewable energy alternatives.<sup>1-3</sup> Abundantly available, solar

t Electronic Supplementary Information (ESI) available: Polarization curves of MoS<sub>2</sub> at different rpms; Koutecky–Levich plots, CV of ferrocene, CVs of MoS<sub>2</sub> precursors in DMF, Polarization curves of MoS<sub>2</sub>/FTO, CVs of bare FTO, as-grown and N<sub>2</sub>-annealed MoS<sub>2</sub> at different scan rates, CVs by Pt electrode for ORR activity from N<sub>2</sub>-saturated, freshly-prepared and O<sub>2</sub>-saturated Na<sub>2</sub>SO<sub>4</sub> electrolytes at different scan rates, EDS of Cu<sub>2</sub>O and MoS<sub>2</sub>/Cu<sub>2</sub>O, EDS mapping of cross-sectional MoS<sub>2</sub>/Cu<sub>2</sub>O, SEM of N<sub>2</sub>-annealed Cu<sub>2</sub>O and MoS<sub>2</sub>, Photocurrents of N<sub>2</sub>-annealed MoS<sub>2</sub>-modified Cu<sub>2</sub>O inth varying MoS<sub>2</sub> layers, XRD and SEM of N<sub>2</sub>-annealed Cu<sub>2</sub>O before and after PEC, Photocurrents of as-grown MoS<sub>2</sub>-modified Cu<sub>2</sub>O, IPCE under backside illumination, Long-term photostability tests of as-grown Cu<sub>2</sub>O and No<sub>2</sub>-annealed MoS<sub>2</sub>-modified Cu<sub>2</sub>O, XRD patterns and SEM images of as-grown Cu<sub>2</sub>O and N<sub>2</sub>-annealed MoS<sub>2</sub>-modified Cu<sub>2</sub>O, XRD patterns and after 1 h stability test. See DOI: 10.1039/x0xx00000x



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exploited as a hole transport layer in planar *p-i-n* junction perovskite solar cells leading to high conversion efficiencies.<sup>19</sup> Additional merits

## Table 1 Recent literature on protected Cu<sub>2</sub>O photocathode for solar water splitting

#	Cu <sub>2</sub> O	Protective layer(s)	PEC Performance	Reference
1	Electrodeposition (lactate bath) 1.3 µm thick	5 nm Al:ZnO+11 nm TiO <sub>2</sub> by ALD and Pt NPs by electrodeposition (ED) (on FTO)	$J_{\rm ph}{=}{-}7.60~{\rm mA~cm}^{-2}$ @0 $V_{\rm RHE}$ from 1.0 M $Na_2SO_4$ buffered at pH 4.9 with 0.1 M KPi.	Nat. Mater. <sup>13</sup>
2	Electrodeposition (lactate bath) 200 nm thick	20 nm Al:ZnO+100 nm TiO <sub>2</sub> by ALD, 40 nm RuO <sub>x</sub> by photodeposition on Au, NiO, and NiO/CuO-coated FTO substrates	$J_{ph}$ =-5.20 mA cm <sup>-2</sup> @0 V <sub>RHE</sub> from 0.5 M Na <sub>2</sub> SO <sub>4</sub> and 0.1 M KPi at pH 5.0.	Energy Environ. Sci <sup>20</sup>
3	Electrodeposition (lactate bath) 500 nm thick	20 nm Al:ZnO+100 nm TiO <sub>2</sub> by ALD, 40 nm RuO <sub>x</sub> by photodeposition and Pt NPs by ED (on FTO)	$J_{ph}$ =–5.00 mA cm <sup>-2</sup> @0 V <sub>RHE</sub> from 1.0 M Na <sub>2</sub> SO <sub>4</sub> buffered at pH 5.0 with 0.1 M KPi.	Energy Environ. Sci. <sup>21</sup>
4	Electrodeposition (lactate bath) 500 nm thick	Amorphous MoS <sub>2</sub> : 20 nm Al:ZnO +100 nm TiO <sub>2</sub> by ALD and 100 nm MoS <sub>2</sub> by CV from 0.2 mM aqueous solution of $(NH_4)_2MoS_4 + 0.1$ M NaClO <sub>4</sub> (pH 6.8) and Pt NPs by ED (on FTO)	$\label{eq:Jph} \begin{split} J_{ph} = & -2.70 \text{ mA cm}^{-2} @0 \text{ V}_{\text{RHE}} \text{ from } 1.0 \text{ M} \\ \text{Na}_2 \text{SO}_4 \text{ buffered at pH 5.0 with } 0.1 \text{M} \\ \text{K}_3 \text{PO}_4 \text{ and } -5.70 \text{ mA cm}^{-2} @0 \text{ V}_{\text{RHE}} \text{ from} \\ \text{H}_2 \text{SO}_4 \text{ at pH 1.0} \end{split}$	Nat. Commun. <sup>22</sup>
5	Anodization, Cu(OH)2/Cu to Cu2O NWs	20 nm Ga <sub>2</sub> O <sub>3</sub> +15 nm TiO <sub>2</sub> by ALD (annealed at 220°C) and Pt NPs by ED	$J_{ph}$ =-2.95 mA cm <sup>-2</sup> @0 V <sub>RHE</sub> from 0.5 M Na <sub>2</sub> SO <sub>4</sub> -0.1 M KH <sub>2</sub> PO <sub>4</sub> buffered at pH 4.3.	Energy Environ. Sci. <sup>23</sup>
6	Anodization Cu(OH) <sub>2</sub>	Graphene: Cu(OH) <sub>2</sub> NWA/Cu mesh in aqueous GO dispersion solution (20 min), dried, annealed at $500^{\circ}$ C in an N <sub>2</sub> for 4 h (on Cu mesh)	$J_{ph}$ =-4.80 mA cm <sup>-2</sup> @0 V <sub>RHE</sub> from 1.0 M Na <sub>2</sub> SO <sub>4</sub> buffered at pH 5.0 with 0.1 M KPi.	J. Mater. Chem. A <sup>24</sup>
7	Electrodeposition (lactate bath) 2.3 µm thick	$2.7~\mu m$ thick porous $Cu_2MoS_4$ by drop-casting and 32 nm NiO by spin-coating 0.5 M Ni(OAc)_2 in 2-methoxyethanol, air-annealing at 220°C for 30 min (on FTO)	$J_{ph}$ =-1.25 mA cm <sup>-2</sup> @0 V <sub>RHE</sub> from 1.0 M Na <sub>2</sub> SO <sub>4</sub> buffered at pH 5.0 with NaHSO <sub>4</sub> .	Nanoscale <sup>25</sup>
8	Electrodeposition (lactate bath) 1.3 μm thick	NiFe-LDH from 0.2 M [Ni(NO <sub>3</sub> ) <sub>2</sub> ·6H <sub>2</sub> O] and 0.1 M [Fe(NO <sub>3</sub> ) <sub>3</sub> ·9H <sub>2</sub> O] at $-1.0$ V vs. Ag/AgCl for few 20 s (on FTO)	$J_{ph}=\sim-2.50 \text{ mA cm}^{-2} @0 \text{ V}_{RHE}$ (At -0.6V <sub>Ag/AgCI</sub> ) from 0.5 M Na <sub>2</sub> SO <sub>4</sub> at pH 6.8 without buffer.	Sci. Rep. <sup>26</sup>

such as low-cost and proper straddling of its energy bands for the water reduction and oxidation potential levels make Cu<sub>2</sub>O an attractive photocathode to achieve visible-light-driven proton reduction for producing H<sub>2</sub> from water. Unfortunately, the use of Cu<sub>2</sub>O as a photocathode for water reduction is hindered by its poor stability in aqueous solution. Both redox potentials for reducing Cu<sub>2</sub>O to Cu and oxidizing Cu<sub>2</sub>O to CuO lie within the bandgap of Cu<sub>2</sub>O, limiting its durability for PEC energy conversion. Several methodologies have been developed to address the stability issue of Cu<sub>2</sub>O (Table 1). For example, ultrathin Al:ZnO interlayer and a few nm TiO<sub>2</sub> coated with RuO<sub>x</sub> or MoS<sub>2</sub> and Pt nanoparticles (NPs) have been used to modify the surface of electrodeposited Cu<sub>2</sub>O to reduce its decomposition during water reduction reaction and enhance the photocurrent up to 7 mA  $\text{cm}^{-2}$  at 0 V versus reversible hydrogen electrode (RHE).<sup>13, 21, 22</sup> ALD coating of  $Ga_2O_3$  thin film buffer layer resulted in a stable performance from TiO2coated Cu<sub>2</sub>O-based photocathodes with higher photovoltage and positive onset potential.<sup>23</sup> Pt NPs are used as co-catalysts in these studies for hydrogen evolution reaction (HER), although large-scale applications of expensive precious metals

in such PEC solar fuel system are severely limited. Pt-free materials such as graphene oxide, porous Cu<sub>2</sub>MoS<sub>4</sub> followed by NiO layer and NiFe layered double hydroxide (LDH) structures have been developed to partially address the stability issue of Cu<sub>2</sub>O.<sup>24-26</sup> Recently, Grätzel group reported a photocurrent density of 5.2 mA cm<sup>-2</sup> at 0 V vs. RHE using a slightly modified Pt-free approach that makes use of a hole-selective under layer of NiO/CuO on FTO substrate.<sup>20</sup> Transition metal dichalcogenides (TMDs), such as molybdenum sulfide (MoS<sub>2</sub>) and tungsten sulfide (WS2), have shown good prospects as electrocatalyst for HER<sup>27-34</sup> and they can serve as a surface protection layer on Cu2O to facilitate efficient charge separation from Cu<sub>2</sub>O and rapid electron transfer to the catalytically active S sites of TMDs for enhanced HER. Recently, Sb<sub>2</sub>Se<sub>3</sub><sup>35</sup> and WSe<sub>2</sub><sup>36</sup> have been explored as the promising binary photocathode materials for efficient solar hydrogen production. Herein, we report a simple synthesis and strategic coating approach by which MoS2 coating is achieved on electrodeposited Cu<sub>2</sub>O using a precursor derivative of molybdenum sulfide [Mo<sub>3</sub>S<sub>7</sub>(S<sub>2</sub>CNEt<sub>2</sub>)<sub>3</sub>]I that can be easily spincoated while maintaining good adherence to the Cu<sub>2</sub>O to

protect its surface and enhance PEC activity. Fig. 1 shows the molecular structure of  $[Mo_3S_7(S_2CNEt_2)_3]I$  precursor and a schematic of solar water splitting system to generate hydrogen using  $MoS_2$ -modified  $Cu_2O$  photocathode. With the catalytically active, protective and stable  $MoS_2$  coating achieved from such precursor, the photo-generated electrons can be



Fig. 1 Schematic of a synthesis strategy to prepare surface-passivated Cu<sub>2</sub>O photocathode (MoS<sub>2</sub>/Cu<sub>2</sub>O/FTO) using MoS<sub>2</sub> (molecular structure of MoS<sub>2</sub> precursor is shown) as a bifunctional material to protect Cu<sub>2</sub>O and perform HER catalysis for solar water splitting application.

effectively transported from the light-absorbing Cu<sub>2</sub>O to the catalytic sites of MoS<sub>2</sub>, which can catalyze the reduction of protons to produce hydrogen while preventing corrosion of Cu<sub>2</sub>O. Such synthetic and coating approach for MoS<sub>2</sub> offer a solution for large-scale production of dual functional MoS<sub>2</sub>/Cu<sub>2</sub>O photocathode for overall PEC water splitting with solar energy.

## Experimental

#### Materials

Copper sulfate anhydrous (CuSO<sub>4</sub>, 98%, ACROS), lactic acid (C<sub>3</sub>H<sub>6</sub>O<sub>3</sub>, 85.0-90.0%, Alfa Aesar), sodium hydroxide (NaOH beads, VWR), sodium sulfate anhydrous (Na<sub>2</sub>SO<sub>4</sub>, 99%, Fisher Scientific), acetone, absolute ethanol, and ethanol, tetrahydrofuran (THF) were used as-received without further purification. All the solutions were freshly prepared using deionized water (resistivity <18 MΩ·cm). Commercially available transparent conducting fluorine-doped tin oxide (FTO, 15-20  $\Omega$ ·cm<sup>-1</sup>, 1.5 × 1.5 cm<sup>2</sup>) coated glass substrates were used.

## Electrodeposition of Cu<sub>2</sub>O films

Prior to electrodeposition, the FTO substrates were cleaned successively using detergent followed by acetone, ethanol and deionized water in an ultrasonic bath each for 10 min, dried

using a N<sub>2</sub> gas stream, and finally treated by UV-ozone for 15 min. Electrodeposition of Cu<sub>2</sub>O was carried out using a slightly modified method reported in the literature.<sup>16</sup> Briefly, Cu<sub>2</sub>O was electrodeposited from a lactate-stabilized solution (pH 11.0) consisting of 0.4 M CuSO<sub>4</sub> and 3.0 M lactic acid using an electrochemical workstation CHI760C (CH Instruments, Inc., Austin, TX) at room temperature in a three-electrode configuration with FTO glass substrate as working electrode, and platinum coil as a quasi-reference electrode. Cu<sub>2</sub>O was deposited at -0.3 V vs. Pt with a total charge of ~4.5 C for optimal film thickness (few µm).

#### Synthesis of MoS<sub>2</sub> precursor derivatives and MoS<sub>2</sub> coating on Cu<sub>2</sub>O

The solvents employed for synthesis of MoS<sub>2</sub> precursor derivatives were dried with a system of drying columns from the Glass Contour Company (CH<sub>2</sub>Cl<sub>2</sub>, hexanes), purchased in an ultra-dry grade (N, N-dimethylformamide), or simply used as received from commercial sources. Tetraethylthiuram disulfide was also used as supplied from a commercial vendor. Literature procedures were used in the preparations of  $[NH_4]_2[Mo_3S_{13}]^{37}$  and  $[Mo_3S_7(S_2CNEt_2)_3]I.^{38}$  The related dimethyldithiocarbate derivative, [Mo<sub>3</sub>S<sub>7</sub>(S<sub>2</sub>CNMe<sub>2</sub>)<sub>3</sub>]I, was also prepared by the method of Hegetschweiler and  $coworkers^{38}$  but from  $[Ph_4P]_2[Mo_3S_7Br_6]$  rather than  $[Et_4N]_2[Mo_3S_7Br_6]$ . The  $[Bu_4N]^+$  salt of  $[Mo_3S_{13}]^{2-}$  was prepared from  $[\mathsf{NH}_4]_2[\mathsf{MO}_3\mathsf{S}_{13}]$  by base neutralization with  $[\mathsf{Bu}_4\mathsf{N}][\mathsf{OH}]$  , as coworkers.<sup>39</sup> described by McDonald and The  $[Mo_3S_7(S_2CNEt_2)_3]^+$  cation can be prepared either by displacement of  $Br^{-}$  from  $[Mo_3S_7Br_6]^{2-}$  by the dithiocarbamate anion or by oxidation and displacement of terminal disulfide with the tetrathiuram disulfide (Scheme 1). This compound type crystallizes well and in reproducible fashion with the I counteranion, which forms particularly favorable  $S_{ax}$ ...I softsoft interactions on the underside of the cluster opposite the  $\mu_{3-}$ sulfide ligand, Scheme 1D). The structure of the  $[Mo_3S_7(S_2CNEt_2)_3]^+$  cation reveals an idealized  $C_{3v}$  symmetry in multiple independent X-ray diffraction studies with varying counteranions.  $(I^{-,38, 40, 41}, Br^{-,42}, CI^{-,43}, CIO_4^{-,40}, \%S^{2-,44})$ -S<sub>2</sub>CNEt<sub>2</sub>,<sup>45</sup> TCNQ<sup>46</sup> (TCNQ= tetracyanoquinodimethane)). Electrochemical characteristics of [Mo<sub>3</sub>S<sub>7</sub>(S<sub>2</sub>CNEt<sub>2</sub>)<sub>3</sub>]I are described in the Supporting Information, (Fig. S1 and S2). To achieve MoS<sub>2</sub> coating on Cu<sub>2</sub>O films, first, the precursor was dissolved in an appropriate solvent and spin-coated onto Cu<sub>2</sub>O films. The desired MoS<sub>2</sub> coating thickness was



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Scheme 1 Synthesis of (C)  $[Mo_3S7(S_2CNEt_2)_3]I$  cluster from either (A)  $[Mo_3S_{13}]^{2^-}$  or (B)  $[Mo_3S_7Br_6]^{2^-}$ . Image (D) shows an orientation of  $[Mo_3S_7(S_2CNEt_2)_3]I$  with the  $Mo_3$  plane orthogonal to the plane of the paper.

optimized by adjusting the precursor concentration as well as number of spin-coated layers.

# Characterization of $[Mo_3S_7(S_2CNEt_2)_3]I$ decomposition and fabrication of $MoS_2$ electrodes

The thermal behavior of as-synthesized  $[Mo_3S_7(S_2CNEt_2)_3]I$  The TGA/DSC measurements were performed by heating the powder in an Al<sub>2</sub>O<sub>3</sub> crucible under flowing argon at a heating rate of 2 °C min<sup>-1</sup> from room temperature to 600 °C. The structural analysis of as-grown Cu<sub>2</sub>O and N<sub>2</sub>-annealed MoS<sub>2</sub>- a thermogravimetric analyzer (SETARAM SETSYS), which performed thermogravimetric analysis (TGA) and differential powder (a precursor for coating MoS<sub>2</sub> film) was examined using scanning calorimetry (DSC) simultaneously. coated Cu<sub>2</sub>O samples was performed using a Bruker D8 Discover X-ray diffractometer equipped with Co-Ka radiation source operated at 40 kV and 30 mA. The X-ray diffraction (XRD) patterns were recorded in the  $2\theta$  range of 20-100°. The phase identification was done using Bruker GADDS software with the help of a standard diffraction database (ICDD). The surface and crosssectional morphology, and the chemical composition of films were examined using a JEOL 700 scanning electron microscope (SEM) equipped with an X-ray energy dispersive spectrometer (EDS). High-resolution transmission electron microscopy (HRTEM) images of Cu<sub>2</sub>O and MoS<sub>2</sub>-modified Cu<sub>2</sub>O were acquired from a FEI TECNAI F20 transmission electron microscope. A TESCAN LYRA focus ion beam-field emission scanning electron microscope (FIB-FESEM) was used to image the surface topography of MoS<sub>2</sub> on FTO. To prepare a FIB specimen for thickness measurement of 3-layered MoS<sub>2</sub> spincoated on FTO, a platinum bar was deposited on top of MoS<sub>2</sub> through a gas injection system to lift it out using omniprobe and attach on a copper grid for the TEM measurement. The

extracted wedge was thinned to a thickness of less than ~100 nm. A FEI TECNAI F20 TEM beam was accelerated at 200 kV to obtain bright field images and diffraction patterns. Raman spectra were recorded with a Horiba LabRAM HR Evolution Raman spectrometer system in the air at room temperature using a 633-nm wavelength laser. The laser was focused onto the sample using a 100X objective. An ultra-low frequency (ULF) filter and a grating with 1800 grooves/mm were used. The rotating ring disc electrode (RRDE), polarization and photocurrent measurements were performed using an electrochemical workstation (CHI 760C, CH Instruments). The RRDE voltammograms were recorded on a RRDE configuration (ALS Co., Ltd, Japan) with a glassy carbon (GC) disc and Pt ring electrode. The geometric area of Pt ring was 0.75 cm<sup>2</sup> (ID=0.5 cm and OD=0.7 cm). The GC disc with a geometric area of 0.50 cm<sup>2</sup> was used as the substrate for deposition of MoS<sub>2</sub> catalyst. Prior to catalyst deposition, the RRDE was initially polished with a 0.3  $\mu$ m alumina (Buehler) slurry on a Nylon pad and subsequently with 0.05  $\mu$ m alumina slurry on a micro-cloth (CH Instruments) and then cleaned with deionized water ultrasonically. MoS<sub>2</sub> electrocatalyst was prepared on GCE by drop-casting and air-drying a microliter drop of 5 mM MoS<sub>2</sub> precursor solution in THF. The HER activity of MoS<sub>2</sub> was tested in 0.5 M H<sub>2</sub>SO<sub>4</sub> electrolyte using RRDE voltammograms recorded at the rotation frequencies from 0 to 5000 rpm. The potential range for HER scans is chosen such that excessive H<sub>2</sub> bubbling is avoided. All electrochemical, as well as PEC measurements, were carried out at room temperatures in a three-electrode system consisting of photocathode as the working electrode, a saturated calomel electrode (SCE, sat. KCl) or silver/silver chloride (Ag/AgCl, sat. KCI) as reference electrode, and a counter electrode such as platinum. Unless otherwise specified, all potentials in this work are measured against the SCE or Ag/AgCl reference electrodes and are reported versus reversible hydrogen electrode (RHE) using Nernst equation (1):<sup>47</sup>,

 $E_{\rm RHE} = E_{\rm Reference} + 0.059 \,\,\mathrm{pH} + E_{\rm Reference}^{\rm o} \tag{1}$ 

where  $E_{\rm RHE}$  is the converted potential vs. RHE,  $E_{\rm Reference}$  is the experimental potential measured against the reference electrode (SCE or Ag/AgCl), and  $E_{Reference}^{o}$  is the standard potential of refthe erence electrode (0.242 V for SCE and 0.1976 V for Ag/AgCl at 25 °C). Cyclic voltammograms (CVs) were recorded for proton reduction studies using MoS<sub>2</sub>-coated glassy carbon or FTO electrodes in 0.5 M H<sub>2</sub>SO<sub>4</sub> electrolyte at the scan rate of 50 mV s<sup>-1</sup>. All CVs were all corrected for the *iR* contribution using CHI instrument. The photoelectrochemical measurements of as-grown and MoS2-modified Cu2O photocathodes were performed in 0.5 M Na<sub>2</sub>SO<sub>4</sub> electrolyte (pH 6.7). Alternatively, CVs were recorded for FTO, as-grown and N<sub>2</sub>-annealed MoS<sub>2</sub>/FTO, and Pt disc electrode (2 mm diameter) to investigate the proton reduction and/or oxygen reduction reaction (ORR). Unless otherwise mentioned, all the PEC or electrochemical (ORR/HER) measurements using MoS<sub>2</sub>, MoS2-modified Cu2O or Pt electrodes were performed in aerobic (freshly-prepared or  $O_2$ -saturated) and anaerobic ( $N_2$ saturated) near-neutral 0.5 M Na<sub>2</sub>SO<sub>4</sub> electrolytes at room temperature. High-purity  $N_2$  or  $O_2$  gases were rigorously purged into the electrolyte for at least one hour at the rate of  $30 \text{ mL min}^{-1}$ . The electrolyte was deaerated with high-purity N<sub>2</sub> to eliminate the effect of oxygen reduction. Although MoS<sub>2</sub> is known as HER catalyst like Pt, we also explored its ability as cata alyst for oxygen reduction reaction (ORR) since 2dimensional (2D) MoS<sub>2</sub><sup>48</sup> has recently shown such ORR activity when combined with carbon-based electrodes.<sup>49</sup> A standard simulated 1 sun (intensity of 100 mW cm<sup>-2</sup>) irradiation was provided with the help of a solar simulator using a 300 W xenon lamp (Oriel AM 1.5 filtered, Newport) light source. The J-V curves of photocathodes were recorded using linear sweep voltammetry (LSV) at a scan rate of 50 mV s<sup>-1</sup> under chopped light at a frequency of 2.5 Hz with front-side illumination. Incident photon to light conversion efficiency (IPCE) or action spectra were measured using the same xenon lamp and a monochromator in the wavelength range of 400-700 nm. The photocathode was fixed inside a three-arm PEC cell and illuminated from the substrate side (backside) as well as the film side (frontside). The photocurrent responses at each wavelength were collected by measuring chronoamperometric J-t curves in a three-electrode configuration at ~0.2 V vs. RHE in 0.5 M Na<sub>2</sub>SO<sub>4</sub>. The power density of the monochromatic light was measured using a calibrated silicon photodiode (THORLABS, S110C) to determine the IPCE values at each wavelength. Electrochemical impedance spectroscopy (EIS) and Mott-Schottky (MS) studies were performed using the same electrochemical workstation (CHI 760C), which is equipped with an electrochemical interface and impedance analyser facility. The EIS curves were recorded from 100 kHz to 0.1 Hz at the water reduction potential of 0.0 V vs. RHE (-0.6 V vs. Ag/AgCl) under 1 sun illumination. A ZView program (Scribner Associates Inc.) was used to fit the EIS data with a

suitable equivalent circuit model. The MS measurements were performed in the dark by sweeping a DC potential from -0.5 to 0.2 V vs. Ag/AgCl at an AC frequency of 1 kHz. The amplitude of AC signal was 10 mV for both EIS and MS measurements. Optical absorption of the films was studied (wavelength range: 400-700 nm) using a UV-vis spectrophotometer (Perkin Elmer Lambda 35).

#### **Results and Discussion**

To quickly gain insight into the HER electrocatalytic activity of MoS2 derived from [Mo<sub>3</sub>S<sub>7</sub>(S<sub>2</sub>CNEt<sub>2</sub>)<sub>3</sub>]I precursor, rotating ring-disc electrode (RRDE) voltammograms were carried out based on a RRDE configuration with a glassy carbon disc electrode (GCE) and Pt ring electrode. Fig. 2A shows the polarization curves for HER of GCE and MoS2-modified GCE recorded at 5000 rpm in 0.5 M  $H_2SO_4$  electrolyte. The protons are reduced on the glassy carbon disc (with or without  $MoS_x$ coating) resulting in HER current and are then oxidized at the Pt ring, as shown schematically in the inset of Fig. 2A, to produce oxidation current. Pt ring electrode potential was held constant at 0.4 V vs. SCE (0.65 V vs. RHE), which is sufficiently positive to oxidize hydrogen from the GC disc electrode. Both disc and ring current densities of MoS2-modified GCE are remarkably higher than those of GCE. For better HER or ORR activity, the catalyst should have a lower overpotential, which is basically the difference between the applied potential and the



Fig. 2 (A) RRDE response (rotation speed 5000 rpm) for bare GCE and 5.0 mM  $MoS_2/GCE$ ; Inset shows the Tafel slope for each electrode. (B) Polarization curves of asgrown and N<sub>2</sub>-annealed  $MoS_2/FTO$  electrodes for proton reduction. Scan rate: 50 mV s<sup>-1</sup>; Electrolyte: 0.5 M H<sub>2</sub>SO<sub>4</sub>.

thermodynamic potentials of a given electrochemical reaction. The polarization curves are replotted as overpotential ( $\eta$ ) against the logarithm of current density (log J) in the inset of Fig. 2A to obtain Tafel plots for assessing the HER kinetics of MoS<sub>2</sub>- modified GC electrode. The Tafel slope is an intrinsic property of an electrocatalyst and can be used to probe the elementary steps involved in H<sub>2</sub> evolution, providing insights into the HER mechanism. The linear portion of the Tafel plots

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are fit to the Tafel equation ( $\eta$ =  $b \log J/J_0$ , where J is the current density,  $J_0$  is the exchange current density, and b is the Tafel slope), yielding Tafel slopes of about 79 and 175 mV  $dec^{-1}$  for MoS<sub>2</sub>/GCE and bare GCE, respectively. The lower Tafel slope of 79 mV dec<sup>-1</sup> and higher exchange current density of 1.31 mA  $cm^{-2}$  for MoS<sub>2</sub>/GCE as compared to bare GCE ( $b=175 \text{ mV dec}^{-1}$  and  $J_0=0.04 \text{ mA cm}^{-2}$ ) strongly suggest that  $MoS_2$  prepared from  $[Mo_3S_7(S_2CNEt_2)_3]$  is a promising HER catalyst. The onset potential for HER activity for such MoS<sub>x</sub> is around -0.2 V vs. RHE, which is better than the MoS<sub>2</sub> nanosheets and close to the state of the art Pt/C catalyst tested using RRDE (~0 V vs. RHE).<sup>50</sup> Generally, Gibb's free energy change  $(\Delta G_H)$  is regarded as a reasonable descriptor of HER activity for a wide variety of catalysts and it is suggested to have optimum HER activity at  $\Delta G_{H} \approx 0$ . The lower  $\Delta G_{H}$  can lead to very high surface coverage of  $H_{ads}$ , while higher  $\Delta G_H$ will cause the protons to be bonded too weakly on the catalyst surface, which both lead to sluggish HER kinetics. Both density functional theory (DFT)<sup>32</sup> calculations and experimental<sup>51</sup> studies have shown that the MoS<sub>2</sub> edge sites with unsaturated sulfur atoms can lower the  $\Delta G_{H}$  approaching 0. The MoS<sub>2</sub> reduces the protons at low overpotential via coordinated sulfur edge sites  $((10\overline{10})$  planes on edges of MoS<sub>2</sub>), while its basal (0001) planes are catalytically inactive.<sup>51</sup> Thus, nanocrystalline  $MoS_2$  with copiously exposed S edges is more active for HER than its inert bulk forms. This understanding has led to significant efforts for developing nanostructured MoS<sub>2</sub>based HER catalysts to maximize the number of edge sites, including amorphous, crystalline, and hybrid materials.<sup>52</sup> The HER activity in acidic media is proposed to follow two separate pathways (the Volmer-Tafel or the Volmer-Heyrovsky mechanism) for reducing protons ( $H^+$ ) to hydrogen ( $H_2$ )<sup>52, 53</sup> which proceeds through three possible reaction steps.  $^{\rm 53,\ 54}$ Depending on different Tafel slopes, the rate-limiting steps can be electrochemical hydrogen adsorption,  $H_3O^+ + e^- \rightarrow H_{ads} +$  $H_2O$  (Tafel slope of 120 mV dec<sup>-1</sup>), electrochemical desorption,  $H_{ads} + H_3O^+ + e^- \rightarrow H_2 + H_2O$  (Tafel slope of 40-120 mV dec<sup>-1</sup>), and chemical desorption,  $H_{ads} + H_{ads} \rightarrow H_2$  (Tafel slope of 30-40 mV dec<sup>-1</sup>).<sup>52, 53</sup> The rate-limiting step of HER on our MoS<sub>2</sub> catalyst is electrochemical desorption because of its low Tafel slope. The polarization curves data for MoS<sub>2</sub> on GCE obtained at -0.36 V vs. RHE for different rotation speeds yielded a linear Koutecky-Levich plot over the entire rotation frequency range tested at both disc and ring electrodes (Fig. S3). The slope of Koutecky-Levich plot for MoS<sub>2</sub> on disc electrode is close to one (n=0.95), which suggests that the electrochemical adsorption of hydrogen proceeds at potentials near the onset by consuming one electron and then combining with another adsorbed hydrogen to evolve hydrogen gas at more cathodic potentials. To further





assess the electrocatalytic proton reduction HER activity of MoS<sub>2</sub> upon annealing treatment on transparent conducting substrates, a 5-mM solution of MoS<sub>2</sub> in THF was spin-coated onto the FTO substrates. Electrocatalytic activity for proton reduction by MoS<sub>2</sub> catalyst, before and after annealing at 450 °C in N<sub>2</sub> atmosphere, was investigated by cyclic voltammetry (CV) in 0.5 M H<sub>2</sub>SO<sub>4</sub> electrolyte. In Fig. 2B, the lower Tafel slope of 68 mV dec<sup>-1</sup> with exchange current density of 1.95 mA cm<sup>-2</sup>) for N<sub>2</sub>-annealed MoS<sub>2</sub> as compared to air-dried MoS<sub>2</sub> (*b*=132 mV dec<sup>-1</sup> and *J*<sub>0</sub>=10.28 mA cm<sup>-2</sup>) indicates that spin-coated MoS<sub>2</sub> supports kinetically favorable HER than bare GC electrode. In other words, N<sub>2</sub>-annealed MoS<sub>2</sub>, which requires at least 0.048 V for HER.

The simultaneous TGA/DSC analysis of  $[Mo_3S_7(S_2CNEt_2)_3]I$ in Ar environment was performed to observe the thermolysis of  $[Mo_3S_7(S_2CNEt_2)_3]I$  and the subsequent crystallization behavior of  $MoS_2$ . Fig. 3 shows the TGA/DSC profiles of  $[Mo_3S_7(S_2CNEt_2)_3]I$  under flowing Ar gas. The profiles suggest a series of reactions with continuous weight losses upon heating from room temperature to 600 °C. Five decomposition steps can be identified from the TGA curve with mass loss ratios of 8.2, 18.3, 20.5, 23.3 and 45.8%, respectively. The first decomposition at around 80 °C arises from the dehydration of the starting precursor material, which results in 8.2% mass loss. The second



Fig. 4 Effect of MoS $_2$  film thickness (A) and N $_2$ -annealing temperature (B) on proton reduction current density of MoS $_2/FTO$  electrodes

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in the range of 80-150 °C, causing an accumulated mass loss of 26.5% (8.2%+18.3%), is attributed to the formation of (NH<sub>4</sub>)<sub>2</sub>MoS<sub>4</sub>. For the third decomposition, a mixture of MoS<sub>3</sub>/MoS<sub>2</sub> (in a ratio of 1:1) is likely formed in the temperature range of 150-245 °C leading to a total weight loss of 20.5%, which implies a transition from  $(NH_4)_2MoS_4$  to  $MoS_2$ . In the temperature range of 245-310 °C, the MoS<sub>2</sub> is formed at a mass loss of 23.3%. In the temperature range of 310-462 °C, the crystalline transformation of MoS<sub>2</sub> occurs. However, with a mass loss of 45.8%, MoS<sub>2</sub> is converted into MoO<sub>2</sub> at higher temperatures, possibly due to residual oxygen present in the crucible. The presence of two distinct exothermic peaks at 258 and 325 °C also confirms the phase transformations from amorphous mixed  $(MoS_3+MoS_2)$  to the crystalline  $MoS_2$ material. Hence, the annealing temperature window of 350-450 °C is best suited to produce the crystalline MoS<sub>2</sub> phase.

Fig. 4A shows proton reduction HER characteristics of MoS<sub>2</sub>/FTO electrodes fabricated at 450 °C by spin-coating different concentrations of [Mo<sub>3</sub>S<sub>7</sub>(S<sub>2</sub>CNEt<sub>2</sub>)<sub>3</sub>]I precursor in THF. The precursor concentration was varied from 0.25 to 5.0 mM. MoS<sub>2</sub> film coated from 2.5 mM precursor derivative gives optimal proton reduction performance. Additionally, to determine the appropriate temperature to fabricate active  $MoS_2$  coating, the N<sub>2</sub>-annealing temperature was varied from 350 to 500 °C at intervals of 50 °C by keeping a fixed precursor concentration of 2.5 mM (See Fig. 4B). The annealing study suggests that a MoS<sub>2</sub>/FTO electrode fabricated at 450 °C gives optimum HER performance. Such electrode exhibits a Tafel slope of -40 mV dec<sup>-1</sup> (not shown) and exchange current density of 0.33 mA cm<sup>-2</sup>, which suggests that N<sub>2</sub>-annealed MoS<sub>2</sub> can drive a large catalytic current density (for instance, 10 mA cm<sup>-2</sup>) for a small overpotential of 0.06 V vs. RHE. According to HER kinetic models, a Tafel slope of 40 mV dec<sup>-1</sup>  $(< 120 \text{ mV dec}^{-1})$  for N<sub>2</sub>-annealed MoS<sub>2</sub> in 0.5 M H<sub>2</sub>SO<sub>4</sub> is closer to the lowest value measured till now for MoS<sub>2</sub>-based HER catalysts, even approaching that of  $\sim 30$  mV dec<sup>-1</sup> for Pt/C catalysts<sup>52</sup> and follows a Volmer-Tafel rate-determining step mechanism.<sup>53</sup> Thus, N<sub>2</sub>-annealed MoS<sub>2</sub> exhibits relatively higher electrocatalytic performance as an efficient HER catalyst with lower onset potential, high catalytic exchange current density, and a small Tafel slope. This enhancement can be ascribed to the formation of crystalline MoS<sub>2</sub> with adequate exposure of catalytically active sites. The [Mo<sub>3</sub>S<sub>7</sub>(S<sub>2</sub>CNMe<sub>2</sub>)<sub>3</sub>]I and other derivatives of  $MoS_2$  such as  $Mo_3S_7(S_2CNEt_2)_3I$ ,  $Mo_{3}S_{4}(S_{2}CNEt_{2})_{4},\ (NH_{4})_{2}[Mo_{3}S_{13}],\ \text{and}\ (Bu_{4}N_{2})[Mo_{3}S_{13}]\ \text{were}$ also investigated for the proton reduction. These precursors were dissolved in different solvents such as THF, DMF, or CH<sub>2</sub>Cl<sub>2</sub>, spin-coated onto conducting FTO glass substrates, and N2-annealed at 450 °C for 1 h. Owing to their limited solubility, precursor concentrations of 1.0 mM were employed for all derivatives such that, for purposes of comparison, all MoS<sub>2</sub> films were prepared under a common set of conditions. The proton reduction HER curves for all the derivatives are shown in Fig. S4. Among them, [Mo<sub>3</sub>S<sub>7</sub>(S<sub>2</sub>CNMe<sub>2</sub>)<sub>3</sub>]I prepared from THF exhibited the most promising HER activity. Thus,  $[Mo_3S_7(S_2CNMe_2)_3]I$  was chosen for our further studies with Cu<sub>2</sub>O photocathodes. The catalytic activities of MoS<sub>2</sub>

electrodes prepared with optimal synthesis conditions (2.5 precursor concentration and 450°C mΜ annealing temperature in N<sub>2</sub>) and their counterparts are investigated in a near-neutral 0.5 M Na<sub>2</sub>SO<sub>4</sub> electrolyte and compared with a platinum disc electrode. Fig. S5 shows the corresponding CVs of bare FTO, as-grown MoS<sub>2</sub> (air-dried for 1 min and 15 h), and N<sub>2</sub>-annealed MoS<sub>2</sub> electrodes recorded at the scan rate of 50 mV s<sup>-1</sup> from freshly prepared and 2 h-degassed (O<sub>2</sub>-free) 0.5 M Na<sub>2</sub>SO<sub>4</sub> electrolytes. N<sub>2</sub>-annealed MoS<sub>2</sub>/FTO sample shows better catalytic activity towards proton reduction in N2saturated Na2SO4 electrolyte than the as-synthesized MoS<sub>2</sub>/FTO sample. CVs at different scan rates for all the samples in oxygen-free and oxygenated Na<sub>2</sub>SO<sub>4</sub> electrolyte also show a similar trend (Fig. S6). The ORR and HER activities in oxygen-free and oxygenated near-neutral 0.5 M Na<sub>2</sub>SO<sub>4</sub> are studied using a standard Pt disc electrode at different scan rates (Fig. S7). As seen from the overlay of CVs at the scan rate of 50 mV s<sup>-1</sup> (Fig. S7D), no oxygen reduction peak is seen for oxygenated Na<sub>2</sub>SO<sub>4</sub> electrolyte although the cathodic current density is relatively higher than the background current (O2free N<sub>2</sub>-saturated electrolyte). On the other hand, the proton reduction current density is higher for N2-saturated electrolytes at more electronegative potentials.



Fig. 5 (A) Normalized XRD patterns of as-grown Cu<sub>2</sub>O/FTO, N<sub>2</sub>-annealed Cu<sub>2</sub>O/FTO, and N<sub>2</sub>-annealed MoS<sub>2</sub>/Cu<sub>2</sub>O/FTO electrodes. (B) Surface and cross-sectional SEM images of as-grown Cu<sub>2</sub>O/FTO and N<sub>2</sub>-annealed MoS<sub>2</sub>/Cu<sub>2</sub>O/FTO electrodes.





To study the HER characteristics of MoS<sub>2</sub> film on a different substrate than FTO, we studied the effect of MoS<sub>2</sub> coating on the PEC activities of a Cu<sub>2</sub>O. And the electrodes were characterized by XRD and SEM prior to PEC measurement. Fig. 5A shows the normalized XRD patterns of as-grown Cu<sub>2</sub>O, N<sub>2</sub>annealed Cu<sub>2</sub>O, and N<sub>2</sub>-annealed MoS<sub>2</sub>-modified Cu<sub>2</sub>O films. All the synthesized films are polycrystalline. As-grown Cu<sub>2</sub>O are indexed to the cubic Cu<sub>2</sub>O phase with a lattice constant of a=4.2696 Å. The diffraction peaks of as-grown Cu<sub>2</sub>O at 34.45°, 42.56°, 49.39°, 72.54°, 88° and 93.14° correspond to the diffraction from (110), (111), (200), (220), (311) and (222) planes of Cu<sub>2</sub>O (ICDD PDF#05-0667). No discernible peaks of CuO or Cu are seen. The peaks marked by asterisks are due to the FTO substrate. All the samples exhibit a dominant peak at ~42° indicating highly oriented (111) Cu<sub>2</sub>O plane. N<sub>2</sub>-annealed  $Cu_2O$  and  $MoS_2$ -modified  $Cu_2O$  samples show identical XRD patterns with enhanced crystallinity. N2-annealed MoS2/Cu2O showed no peaks from the thin layer of MoS<sub>2</sub>. Additionally, shift in diffraction peaks towards lower  $2\theta$  angles suggests an increase in lattice parameters, indicative of the expansion of crystal lattice. XRD patterns of annealed samples show sharp and narrow diffraction peaks with an increase in lattice parameter to 4.3108 Å. Annealing causes grain growth and coalesces of grain boundaries resulting in the ordered crystal structure. N<sub>2</sub>-annealed MoS<sub>2</sub>/Cu<sub>2</sub>O shows greater crystallinity as compared to N<sub>2</sub>-annealed Cu<sub>2</sub>O. A larger shift in  $2\theta$  angle at higher angles is an indication of a reduction in the strain of the film. Both the N<sub>2</sub>-annealed samples show no peaks of Cu or CuO. Fig. 5B shows the representative SEM images of as-grown Cu<sub>2</sub>O and N<sub>2</sub>-annealed MoS<sub>2</sub>/Cu<sub>2</sub>O films prepared on FTO. Asgrown Cu<sub>2</sub>O film (~ 2 µm thick) consists of polyhedral cuboidalshaped grains with sharp edges ranging from 1 to 2  $\mu$ m. The SEM image of N2-annealed MoS2/Cu2O film reveals coalescence of grain boundaries. The sharp-edges of cuboidalshaped Cu<sub>2</sub>O grains are covered with a thin film of MoS<sub>2</sub>. The cross-sectional SEM view shows the coverage of thin layer of  $MoS_2$  on ~2  $\mu m$  thick  $Cu_2O$ . The presence of  $MoS_2$  was confirmed from the EDS analysis (Fig. S8). The selective crosssectional area of MoS<sub>2</sub>/Cu<sub>2</sub>O along with EDS mapping (Fig. S9) reveals film а

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**Fig. 7** (A) Photocurrent responses of as-grown Cu<sub>2</sub>O, N<sub>2</sub>-annealed Cu<sub>2</sub>O, and N<sub>2</sub>-annealed 3-layered MoS<sub>2</sub>-modified Cu<sub>2</sub>O photocathodes. The spin-coating layers of 2.5 mM MoS<sub>2</sub> precursor are varied from layer 1 (1L) to layers 4 (4L). (B) IPCE spectra of the Cu<sub>2</sub>O and MoS<sub>2</sub>/Cu<sub>2</sub>O photocathodes at ~0.2 V vs. RHE (-0.4 V vs. SCE) under frontside illumination. The figure also shows the normalized absorbance of as-grown Cu<sub>2</sub>O, MoS<sub>2</sub>, and MoS<sub>2</sub>-modified Cu<sub>2</sub>O films. (C) Nyquist plots of the as-grown Cu<sub>2</sub>O and MoS<sub>2</sub>/Cu<sub>2</sub>O electrodes recorded at a fixed applied potential of -0.6 V vs. Ag/AgCl both in dark and under the light, respectively. The inset shows the equivalent electrochemical circuit to fit the plots. The symbols and the solid lines represent the experimental and fitted data, respectively. (D) Mott-Schottky plots of as-grown Cu<sub>2</sub>O and MoS<sub>2</sub>/Cu<sub>2</sub>O electrodes measured at 1 kHz frequency in dark. Electrolyte: 0.5 M Na<sub>2</sub>SO<sub>4</sub> solution (pH ~6.7); light source: simulated 1 sun (100 mW cm<sup>-2</sup>).

thickness of ~ 40 nm and the presence of all the constituent elements. Assuming a film thickness of 40 nm, the surface coverage of MoS<sub>2</sub> on Cu<sub>2</sub>O is estimated to be 7.6158  $\pm$  0.6  $\times$  10<sup>16</sup> molecules cm<sup>-2</sup> (See Supplementary Information for details). N<sub>2</sub>-annealed 3-layered MoS<sub>2</sub> is alternatively prepared on FTO, which shows continuous coverage of MoS<sub>2</sub> film on SnO<sub>2</sub> crystals (Fig. S10A) The surface morphology of N<sub>2</sub>-annealed Cu<sub>2</sub>O clearly shows the crystal growth (Fig. S10B). A growth of triangular-shaped crystal facets on top of the irregularly shaped crystals can be seen with few multi-faceted white overgrowths.

Fig. 6 shows the linear sweep voltammograms of as-grown  $Cu_2O$  under standard chopped light illumination measured in

0.5 M Na<sub>2</sub>SO<sub>4</sub> for successive six segments. The 1<sup>st</sup> segment has negligible dark current with the onset of photocurrent toward more positive potential. The onset of dark current is at -0.6 V vs. SCE, which reflects the corrosion reaction. Under light illumination, photo-excited electrons of Cu<sub>2</sub>O semiconductor travel to the conduction band of Cu<sub>2</sub>O and reduce protons at the solid-liquid interface to form H<sub>2</sub> gas, while holes travel to counter electrode to oxidize water molecule to produce O<sub>2</sub>. Photocurrent density depends on how effectively the photogenerated electron-hole pairs are separated for the two half-reactions of water splitting without any losses. The photocurrent density measured at 0 V vs. RHE (- 0.59 V vs. SCE) is 2.4 mA cm<sup>-2</sup>, which is in line with the reported literature.<sup>13</sup>

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However, recurring reduction peaks appear at ~0.4 V vs. RHE (-0.15/-0.20 V vs. SCE) during J-V measurements from 2<sup>nd</sup> segment onwards, which is an indication of photo-corrosion because Cu<sub>2</sub>O undergoes reductive decomposition to Cu upon repetitive photocurrent measurements. Such change in the chemical state of the Cu<sub>2</sub>O film after PEC measurement is observed visually by a color change from reddish brown to black and by a decrease in PEC current density. This phenomenon has been previously confirmed by SEM and XPS techniques.<sup>13</sup> Thus, the Cu<sub>2</sub>O layer requires corrosionprotection to avoid direct contact between Cu<sub>2</sub>O and the electrolyte. To suppress the photo-corrosion reaction, we passivated the Cu<sub>2</sub>O surface with a MoS<sub>2</sub> layer to prevent contact with the electrolyte by using a simple approach of spin-coating and thermal annealing treatment. Fig. 7A shows the photocurrent responses of as-grown Cu<sub>2</sub>O, N<sub>2</sub>-annealed Cu<sub>2</sub>O, and N<sub>2</sub>-annealed MoS<sub>2</sub>-modified Cu<sub>2</sub>O (with three spincoated layers of MoS<sub>2</sub>) photocathodes. The photocurrent responses for other layers are shown in Fig. S11A. The photocurrent of  $Cu_2O$  increases significantly with  $MoS_2$ modification. Photocurrent densities of 4.0 mA  $cm^{-2}$  at 0 V vs. RHE and as high as 6.5 mA cm<sup>-2</sup> at -0.2 V vs. RHE are obtained for 3-layered MoS<sub>2</sub>-modified Cu<sub>2</sub>O photocathode. The contribution to the photocurrent due to light absorption by the MoS<sub>2</sub>-protective overlayer is negligible. Additionally, the dark current characteristics of the Cu<sub>2</sub>O photocathodes are improved considerably by extending the dark current onset toward anodic region by 350 mV. The reduction peak observed for as-grown Cu<sub>2</sub>O at 0.4 V vs. RHE (Fig. 6) disappears after being coated with  $\mathsf{MoS}_{2}\text{,}$  indicating that the  $\mathsf{Cu}_2\mathsf{O}$  surface is protected by the  $MoS_2$  layer. The onset of dark current appears at -0.32 V vs. RHE (-0.95 V vs. SCE) that is well below the water reduction potential (0 V vs. RHE) to limit the photocorrosion of Cu<sub>2</sub>O. The enhanced performance of MoS<sub>2</sub>modified Cu<sub>2</sub>O is attributed to uniform coverage of high concentrations of exposed edge-plane structures of MoS<sub>2</sub> on Cu<sub>2</sub>O crystals, which facilitates rapid electron transport leading to significantly elevated catalytic activity. With increasing number of MoS<sub>2</sub> layers, the darkening of the film caused by photo-corrosion is reduced. With increasing MoS<sub>2</sub> thickness beyond 3 layers, however, the photocurrent decreases, which is likely because of blocking of the light by the  $MoS_2$  film and consequent decrease of absorption by the Cu<sub>2</sub>O electrode. The N<sub>2</sub>-annealed Cu<sub>2</sub>O also shows similar photocurrent response at 0 V vs. RHE as that of N<sub>2</sub>-annealed MoS<sub>2</sub>/Cu<sub>2</sub>O. However, its dark current onset is only slightly better than as-grown Cu<sub>2</sub>O. Moreover, its dark current increases after 2<sup>nd</sup> and 3<sup>rd</sup> measurements, eventually decreasing the net photocurrent response (Fig. S11B). The XRD pattern of the N<sub>2</sub>-annealed Cu<sub>2</sub>O sample after the PEC measurements shows the emergence of prominent metallic Cu peaks mainly at 50.55 59.11, and 88.46°, indicating a photo-induced reduction of Cu<sub>2</sub>O to Cu that results in loss of photoactive Cu<sub>2</sub>O material (Fig. S12A). Thus, a decrease in PEC response is due to the photocorrosion of Cu<sub>2</sub>O, which can also be governed by the morphological changes after the PEC measurement (Fig. S12B). The triangular faceted crystals of N2-annealed Cu2O are broken down into

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nanoparticles with porous grain boundaries. Such poor photocurrent response from N2-annealed Cu<sub>2</sub>O could be due to the certain faceted growth of Cu<sub>2</sub>O which is prone to photocorrosion as studied previously.<sup>14, 15</sup> We also investigated the proton reduction performance using 3-layered assynthesized MoS<sub>x</sub> on Cu<sub>2</sub>O in 0.5 M Na<sub>2</sub>SO<sub>4</sub> electrolyte with and without 0.1 M K<sub>2</sub>HPO<sub>4</sub> (Fig. S13). The dramatically higher photocurrent response for MoS<sub>x</sub>-modified Cu<sub>2</sub>O as compared to Cu<sub>2</sub>O as well as N<sub>2</sub>-annealed MoS<sub>2</sub> is encouraging. However, the as-synthesized MoS<sub>x</sub> coating is not adherent and cannot produce similar performance upon repeated measurements. Therefore, the studies using as-synthesized MoS<sub>x</sub> are not carried out further. IPCE is employed as a valuable diagnostic figure of merit for most PEC devices. IPCE values were calculated using relation (2),

IPCE (%) =  $[(1240/\lambda) \times (J_{\text{light}} - J_{\text{dark}})/P_i] \times 100$  (2)

where  $\lambda$  is the wavelength of incident monochromatic light,  $J_{\text{light}}$  is the steady-state photocurrent density at given  $\lambda$ ,  $J_{\text{dark}}$  is the dark current density and  $P_i$  is the power density of incident monochromatic light. Fig. 7B shows the IPCE spectra of Cu<sub>2</sub>O and 3-layered MoS<sub>2</sub>/Cu<sub>2</sub>O photocathodes at ~0.2 V vs. RHE (-0.4 V vs. SCE) under frontside illumination. The figure also shows the absorbance data of Cu<sub>2</sub>O, 3-layered MoS<sub>2</sub>, and 3layered MoS<sub>2</sub>-modified Cu<sub>2</sub>O. The IPCE spectra of Cu<sub>2</sub>O and 3layered  $MoS_2/Cu_2O$ photocathodes under backside illumination are shown in Fig. S14. Relative higher photocurrent response near short wavelength region for the frontside illumination than backside illumination is because of the efficient hole mobility when abundant excited states are produced at the electrode surface upon photoexcitation. Our study shows that MoS<sub>2</sub> modification improves the IPCE under both frontside and backside illuminations. The IPCE spectra reveal that MoS<sub>2</sub>-modified Cu<sub>2</sub>O sample shows a noticeably greater utilization of photons in the wavelength region of 400-600 nm compared to the unmodified Cu<sub>2</sub>O sample because of the improved proton reduction kinetics in the presence of MoS<sub>2</sub>. The higher absorbance for MoS<sub>2</sub>-modified Cu<sub>2</sub>O film is because of the additional absorption of  $MoS_2$ , which is a narrow band gap visible-light absorbing material ( $E_g = 1.8 \text{ eV}$ ) that typically shows absorption peaks in the visible range of 550-700 nm<sup>55</sup>, as also seen from Fig. 7B. The IPCE of any device is closely associated with the photo-absorption ability of the photoactive layer. Electrodeposited Cu<sub>2</sub>O films show an absorption peak at around ~500 nm. However, they are prone to defect formation as in ZnO, which results in deep-level defects such as oxygen vacancies or copper interstitials.<sup>56, 57</sup> These defects enable recombination of charge carriers that causes lower IPCE values. However, MoS<sub>2</sub> serves as a defectpassivating layer on Cu<sub>2</sub>O, which to some extent lowers the charge carrier recombination in the visible region. Thus, higher IPCE of  $MoS_2/Cu_2O$  photocathode can be attributed to the visible light absorption in the higher wavelength spectral region and defect passivating ability of MoS<sub>2</sub>. To further elucidate on the contributing factors toward the photocurrent enhancement, the EIS and MS measurements are performed. EIS analysis sheds light on the charge-transfer processes occurring at the electrolyte interface, while MS analysis

provides information about the nature and concentration of majority charge carriers as well as the built-in voltage of the system. Fig. 7C shows the Nyquist plots of Cu<sub>2</sub>O and 3-layered MoS<sub>2</sub>/Cu<sub>2</sub>O electrodes obtained at -0.6 V Ag/AgCl (~0.0 V vs. RHE) in the dark and under frontside illumination. The Nyquist curves were fitted using an equivalent circuit comprised of a series resistance  $(R_s)$  and two RC (resistance and capacitance) circuits in parallel as shown in the figure inset.  $R_s$  is a sum of all the serial resistances consisting of the electrolyte, contact, electrode and cables. It is noteworthy that the Cu<sub>2</sub>O/FTO electrode shows a higher  $R_s$  value (~420  $\Omega$ ) than that of  $MoS_2/Cu_2O/FTO$  electrode (< 200  $\Omega$ ). Additionally, the chargetransfer resistance  $(R_{ct})$ , typically the diameter of the semicircle, is inversely related to the photocurrent of the PEC system. The corresponding decrease in  $R_{\rm ct}$  value with the addition of MoS<sub>2</sub> as a protecting layer (interfacial layer between Cu<sub>2</sub>O and electrolyte) on Cu<sub>2</sub>O/FTO, both in the dark as well under illumination, implies that charge carrier resistance at the photocathode-electrolyte interface is significantly improved. Under illumination, the R<sub>ct</sub> value decreases considerably from 389 to 178  $\Omega$  after coating the  $MoS_2$  layer onto  $Cu_2O$ . Trap resistance ( $R_{trap}$ ) is one of the important parameters that reveals information about the defect sites in a material. The estimated  $R_{trap}$  values for Cu<sub>2</sub>O in dark and illumination are 262 and 133  $\Omega,$  respectively. Upon MoS<sub>2</sub> coating on Cu<sub>2</sub>O, these values were decreased considerably to 7.5 and 3.8  $\Omega_{\text{r}}$  respectively. Thus defect states are passivated after MoS<sub>2</sub> modification of Cu<sub>2</sub>O. This is an interesting result and more study is necessary because of the electrochemical behavior of Cu<sub>2</sub>O depending on the applied potential and electrolyte. The  $MoS_2$  coating not only protects the surface of Cu<sub>2</sub>O electrode from reductive decomposition but also facilitates the charge transfer properties of Cu<sub>2</sub>O, and hence actively contributes to photocurrent enhancement resulting from PEC water reduction. In other words, MoS<sub>2</sub> passivates the defect states, such as Cu vacancies in Cu<sub>2</sub>O, additionally helping avoid the recombination of charge carriers. Thus, it can be established that MoS<sub>2</sub> at the interface promotes the effective shuttling of the charge carriers at the photocathode-electrolyte interface, which may be due to the formation of nanojunctions.<sup>58</sup> The interfacial space-charge capacitance ( $C_{sc}$ ), which varies as a function of applied potential (V), primarily describes a photoelectrode/electrolyte interface that can be used to estimate the flat band potential and the majority carrier density of a semiconductor from the slope of the MS plot using Eq. (3):59

 $N_{\rm A} = 2/(e_{\rm o}\epsilon\epsilon_{\rm o} |d(C_{\rm sc}^{-2})/dV|) \quad (3)$ 

where  $N_A$  is the acceptor density (hole density in *p*-type Cu<sub>2</sub>O),  $e_o$  is the electron charge,  $\varepsilon_o$  is the permittivity of the vacuum,  $\varepsilon$ is the dielectric constant of the semiconductor (7.60 for Cu<sub>2</sub>O). Fig. 7D shows the MS plots of the Cu<sub>2</sub>O and 3-layered MoS<sub>2</sub>/Cu<sub>2</sub>O electrodes obtained at 1 kHz AC frequency in the dark. The negative slope of the MS plots confirms the *p*-type conductivity of Cu<sub>2</sub>O electrodes. The  $N_A$  value decreases from  $4.5 \times 10^{19}$  cm<sup>-3</sup> to  $2.4 \times 10^{19}$  cm<sup>-3</sup> after coating MoS<sub>2</sub> on Cu<sub>2</sub>O. This can understandably be attributed to the fact that *p*-type conductivity of electrodeposited Cu<sub>2</sub>O originates primarily from defects, such as CuO vacancies. The defects or hole traps 0.40-0.55 eV above the top of the valence band maximum are verified in Cu<sub>2</sub>O. by deep level transient spectroscopy,<sup>57</sup> which are attributed to structural anomalies such as CuO islands.<sup>60</sup> Such defects are passivated after surface coating with MoS<sub>2</sub>, resulting in reduced hole densities. Similar  $N_A$  values are reported in the literature for pristine and protected Cu<sub>2</sub>O electrodes.<sup>61, 62</sup> The extrapolated straight portion of the MS plot on the x-axis at  $C_{sc}$ =0 gives the flat band potential ( $E_{fb}$ ) of the material, which is typically close to the onset potential in the photocurrent response. The  $E_{fb}$  values are close to the onset potentials of Cu<sub>2</sub>O and MoS<sub>2</sub>/Cu<sub>2</sub>O as seen in Fig. 7A. No noticeable change in  $E_{fb}$  is observed after MoS<sub>2</sub> coating. The  $E_{fb}$  value for both the Cu<sub>2</sub>O and MoS<sub>2</sub>/Cu<sub>2</sub>O electrodes is 0.63 ± 0.005 V vs. RHE, which is in line with the reported values.<sup>59, 62</sup>

Fig. 8A shows the photographs of as-grown Cu<sub>2</sub>O and N<sub>2</sub>annealed MoS<sub>2</sub>-modified Cu<sub>2</sub>O photocathodes with different numbers of spin-coated layers, both before and after the PEC measurement. It is evident that the color of the Cu<sub>2</sub>O film area performing the water reduction reaction is unchanged after PEC measurement with increasing number of spin-coated layers of



Fig. 8 (A) Photographs of as-grown Cu<sub>2</sub>O and N<sub>2</sub>-annealed MoS<sub>2</sub>-modified Cu<sub>2</sub>O samples before and after the PEC measurements. The color change from reddish brown to black indicates reductive photodecomposition of Cu<sub>2</sub>O to Cu/CuO. (B) Chronoamperometric responses of as-grown Cu<sub>2</sub>O and MoS<sub>2</sub>-modified Cu<sub>2</sub>O photocathodes at an applied potential of 0 V vs. RHE in 0.1 M phosphate buffered (pH 7) 0.5 M Na<sub>2</sub>SO<sub>4</sub> electrolyte.

 $MoS_2$ . In other words, the  $MoS_2$  layer passivates the reductive photo-decomposition of  $Cu_2O$  to Cu or/and CuO and protects the chemical state of the electrode, resulting in improved PEC water reduction performance. Fig. 8B shows the current transient responses of as-grown  $Cu_2O$  and  $MoS_2$ -modified  $Cu_2O$  electrodes recorded with chopped and steady 1 sun light illumination in a buffered 0.5 M  $Na_2SO_4$  electrolyte at a

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constant potential of -0.6 V vs. SCE (0 V vs. RHE). The photocurrent of Cu<sub>2</sub>O degrades rapidly in first two min and gradually decreases further. The percentage decrease of photocurrent for Cu<sub>2</sub>O and MoS<sub>2</sub>-modified Cu<sub>2</sub>O electrodes after 10 min is 77 and 9%, respectively. Thus, MoS<sub>2</sub>-modified Cu<sub>2</sub>O is about 8 times more stable than pristine Cu<sub>2</sub>O, suggesting that MoS<sub>2</sub> protects Cu<sub>2</sub>O from photo-corrosion making it more durable. With a new set of samples, the longterm photostability tests under 1 sun illumination are performed for 1 h in the same buffered electrolyte as shown in Fig. S15. At the end of the stability test, the light was chopped ON and OFF to observe the light and dark responses of the photocathodes. It is clear that  $MoS_2$ -modified  $Cu_2O$  is relatively more stable than the as-grown Cu<sub>2</sub>O photocathode. As-grown Cu<sub>2</sub>O shows huge dark current with declined photocurrent at the end of 1 h stability test whereas MoS2-modified Cu2O still shows negligibly small dark current with appreciable photocurrent. The net photocurrent density for as-grown Cu<sub>2</sub>O photoelectrode waned down from initial 2.1 to 0.1 mA cm<sup>-2</sup> after 1h illumination whereas it decreased from 3.2 to 1.7 mA  $cm^{-2}$  for MoS<sub>2</sub>-modified Cu<sub>2</sub>O photoelectrode. At the end of stability test, the color of as-grown Cu<sub>2</sub>O turned slightly black unlike MoS<sub>2</sub>-modified Cu<sub>2</sub>O as shown in the inset of the figure. The photogenerated electrons tend to reduce the unprotected Cu<sub>2</sub>O into Cu and photogenerated holes tend to oxidize Cu<sub>2</sub>O into CuO (turning the illuminated area black). Fig. S16 shows the XRD patterns of as-grown Cu<sub>2</sub>O and N<sub>2</sub>-annealed MoS<sub>2</sub>modified Cu<sub>2</sub>O after 1 h stability test. The as-grown Cu<sub>2</sub>O underwent electrochemical transformation by partially reducing Cu<sub>2</sub>O to Cu as two prominent metallic Cu peaks emerge at 50.55 and 59.11°. The reduction of  $Cu_2O$  to Cu in MoS<sub>2</sub>-modified Cu<sub>2</sub>O is less and its XRD pattern after 1 h stability test shows a tiny peak centered at 50.55°. Furthermore, the surface morphologies of as-grown Cu<sub>2</sub>O and MoS<sub>2</sub>-modified Cu<sub>2</sub>O samples before and after the 1 h photostability tests are monitored as shown in Fig. S17. After 1 h illumination, the sharp-edged pyramidal grains of as-grown Cu<sub>2</sub>O are broken down into nanoparticles. Additionally, the grain boundaries are opened allowing the electrolyte to leak to the back contact, consequently yielding an increase in dark current as seen from the stability curve. On the other hand, MoS2-modified Cu2O undergoes relatively less damage with regard to the grain and the grain boundaries although there is some loss of the top layer of the electrode. This observation suggests that the Cu<sub>2</sub>O maintained its oxidized state upon MoS<sub>2</sub>-modification even after 1 h stability test.

Since XRD studies did not reveal any information about the molybdenum sulfide phase on Cu<sub>2</sub>O, we performed HRTEM analysis on the N<sub>2</sub>-annealed MoS<sub>2</sub>-modified Cu<sub>2</sub>O sample. Fig. 9A and 9B show the corresponding HRTEM images of Cu<sub>2</sub>O and MoS<sub>2</sub> along with the selected area electron diffraction (SAED) pattern for molybdenum sulfide. The close match of lattice parameters 0.294 nm (110), 0.212 nm (200), and 0.245 nm (111) with those of Cu<sub>2</sub>O, <sup>63</sup> and 0.270 nm (100) with that of MoS<sub>2</sub> confirmed the formation of MoS<sub>2</sub> on Cu<sub>2</sub>O electrode.



Fig. 9 (A, B) HRTEM images of N<sub>2</sub>-annealed 3-layered MoS<sub>2</sub>-modified Cu<sub>2</sub>O with selected area electron diffraction (SAED) pattern for MoS<sub>2</sub>. (C) Bright field cross-section TEM and HRTEM images of MoS<sub>2</sub> coated on FTO.



Fig. 10 Raman spectra of (A) FTO and N<sub>2</sub>-annealed MoS<sub>2</sub>/FTO, (B) as-grown MoS<sub>2</sub>, as-grown Cu<sub>2</sub>O, as-grown MoS<sub>2</sub>/Cu<sub>2</sub>O, and N<sub>2</sub>-annealed MoS<sub>2</sub>/Cu<sub>2</sub>O samples.

Additionally, the crystallinity of the pristine  $MoS_2$  is further characterized by SAED/FFT patterns. The FFT pattern of  $MoS_2$  with bright spots denotes highly crystalline property and indexes to  $MoS_2$ .<sup>64</sup> To determine the thickness of the  $MoS_2$  layer, the  $MoS_2$  film was alternatively fabricated onto FTO under identical conditions and FIB-TEM analysis was performed. Figure 9B shows a bright field TEM image of  $MoS_2$ /FTO specimen with a platinum cap. The film thickness of 3-layered  $MoS_2$  obtained from the cross-sectional TEM is ~30-40 nm.

Raman spectroscopy is a valuable technique for the identification and characterization of phonon vibrational modes of chemical bonds. Fig. 10A shows the Raman spectra of bare FTO and MoS<sub>2</sub>/FTO samples annealed at 450°C in N<sub>2</sub>. As evident from the figure, dominant optical modes are observed mainly at 380  $\rm cm^{-1}$  and 405  $\rm cm^{-1}$ , which correspond to the Raman-active in-plane  $(E_{2g})$  and out-of-plane  $(A_{1g})$ modes of  $MoS_2$ , respectively. The  $E_{2g}$  mode is sensitive to strain, while the A<sub>1g</sub> mode shows a weak strain dependence.<sup>65</sup> The subtle changes in Raman spectra (minor variations in peak intensity or position) indicate the presence of electronic doping or strain effects.<sup>66</sup> These Raman-active modes are apparently not seen in the as-grown and N2-annealed  $MoS_2/Cu_2O/FTO$  samples (Fig. 10B) possibly due to the dominance of signals from Cu<sub>2</sub>O itself. Collectively, the improved PEC performance by MoS2-modified Cu2O photocathode is attributed to the photocatalytically active polyhedral crystalline morphology of Cu<sub>2</sub>O, the enhanced absorptivity in the visible region, the facilitated separation of electron-hole pairs and the reduced carrier recombination because of decreased interface defects/hole traps in the presence of MoS<sub>2</sub>.

#### Conclusions

In summary, we have demonstrated a MoS<sub>2</sub>-coating technique obtain stable and efficient copper-oxide-based to photocathode materials for PEC hydrogen production. The photocorrosion problem associated with electrodeposited ptype Cu<sub>2</sub>O photocathode is addressed by spin-coating a thin ~40 nm MoS<sub>2</sub> layer onto the surface using a novel MoS<sub>2</sub> precursor complex. The MoS<sub>2</sub> coating not only prevents the reductive photodecomposition of Cu<sub>2</sub>O to Cu but also enhances the overall PEC activity of the photocathode. The catalytic activity of  $MoS_2$  using such complex precursors can readily be tuned by controlling the number of spin-coated layers and the annealing temperature in the N<sub>2</sub> atmosphere. Additionally, the action spectra indicate that the MoS<sub>2</sub> coating helps improve the light absorptivity by  $Cu_2O$  in the visible region. Electrochemical impedance spectroscopy measurements of MoS<sub>2</sub>-modified Cu<sub>2</sub>O suggests improvements in interface properties that lead to enhanced separation of electron-hole pairs as well as reduced carrier recombination because of a decrease in interfacial defects or hole traps. The MoS<sub>2</sub>-modified Cu<sub>2</sub>O photocathodes exhibit photocurrent densities as high as 6.5 mA cm<sup>-2</sup> at -0.2 V vs. RHE in 0.5 M Na<sub>2</sub>SO<sub>4</sub> electrolyte under standard 1 sun illumination conditions, which make them potential candidates for a selfassisted hybrid water splitting system for hydrogen fuel generation. Further work is needed to improve the stability of Cu<sub>2</sub>O photocathode in relatively lower pH media. This work highlights the promise of spin-coatable molybdenum disulfide as a catalytically active thin-film passivation layer for several other unstable semiconductor water-splitting materials. We also envisage that such *p*-type photocathode system can be combined with an *n*-type photoanode system to establish a

cost-effective and efficient unassisted PEC water splitting system to produce hydrogen fuel.

## **Conflicts of interest**

There are no conflicts to declare.

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